	Hits	Search Text	DBs
22	3	((silicon or "Si" or polysilicon or (polycrystalline near4 silicon)) near16 (sputter$4 or PVD or (physical near4 vapor) or (ion near9 beam near9 deposit$4)) near16 (mask or pattern) near16 (conformal$4 or sidewall or side or (vertical near4 side)) near22 ((top near4 surface) or (top near5 side)) near36 (photoresist or resist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
23	28	((silicon or "Si" or polysilicon or (polycrystalline near4 silicon)) near16 (sputter$4 or PVD or (physical near4 vapor) or deposit$4 or coat$4 or (ion near9 beam near9 deposit$4)) near16 (mask or pattern) near16 (conformal$4 or sidewall or side or (vertical near4 side)) near22 ((top near4 surface) or (top near5 side)) near36 (photoresist or resist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
25	0	((silicon or "Si" or polysilicon or (polycrystalline near4 silicon)) near16 (sputter$4 or PVD or (physical near4 vapor) or deposit$4 or coat$4 or (ion near9 beam near9 deposit$4)) near39 (photoresist or resist) near16 (mask or pattern or feature) near16 (conformal$4 or sidewall or side or (vertical near4 side)) near22 ((top near4 surface) or (top near5 side)) near39 (angstrom or nanometer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
26	14	((silicon or "Si" or polysilicon or (polycrystalline near4 silicon)) same (sputter$4 or PVD or (physical near4 vapor) or (ion near9 beam near9 deposit$4)) same (photoresist or resist) same (pattern or mask or feature) same (conformal$4 or sidewall or side or (vertical near4 side)) same ((top near4 surface) or (top near5 side)) same (angstrom or nanometer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB